

18 JUN 2001

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Naomasa SHIRAISHI

Application No.: U. S. National Stage of
PCT/JP99/06962

Filed: June 18, 2001

Docket No.: 109820

For: PRODUCING METHOD AND APPARATUS OF PHOTOMASK

PRELIMINARY AMENDMENTDirector of the U.S. Patent and Trademark Office
Washington, D. C. 20231

Sir:

Prior to initial examination, please amend the above-identified application as follows:

IN THE SPECIFICATION:

Before page 1, line 1, please insert:

--This application is the national phase under 35 U.S.C. § 371 of prior PCT International Application No. PCT/JP99/06962 which has an International filing date of December 10, 1999 which designated the United States of America, the entire contents of which are hereby incorporated by reference.--

Page 5, lines 20-23 to Page 6, lines 1-7, delete current paragraph and insert therefor:

A first producing method of a photomask according to the present invention is a producing method of a photomask on which a pattern to be transferred through a projection optical system under a predetermined first condition is formed, wherein a parent pattern obtained by enlarging the pattern is formed on a first substrate, thereby forming a master